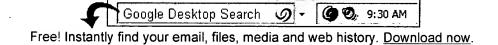


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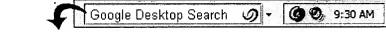
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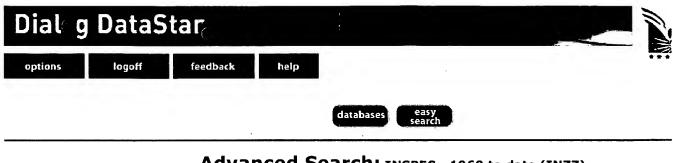
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Schellenberg, F.M.;

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Schellenberg, F.M.; Byer, R.L.;

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VLSI Design, 1999. Proceedings. Twelfth International Conference On

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